



Matthieu Duperron
Photonic Packaging Group
Tyndall National Institute

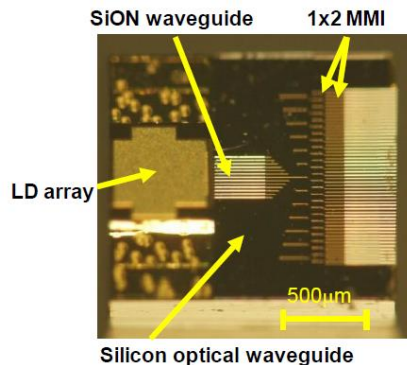
SPIE Photonic West - 1st February 2017

Hybrid Integration of Laser Source on Silicon Photonic Integrated Circuit for a Low-cost Interferometry Medical Device

Introduction: Light Source for Si-PIC

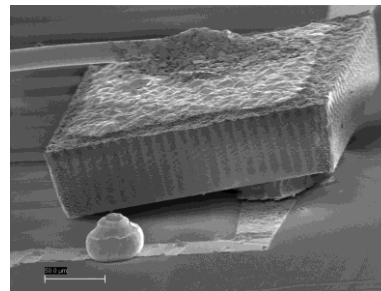
- Photonic Integrated Circuits (PIC) offer integrated, low-cost solution for ICT, sensing and medical applications.
- Need for an "integrated" light source
 - Heterogeneous integration (III-V laser die bonding)
 - Hybrid integration (fully processed laser chip)

Edge coupling *

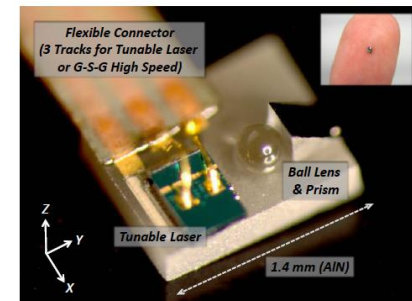


Grating couplers

VCSEL **



Micro-Optical Bench

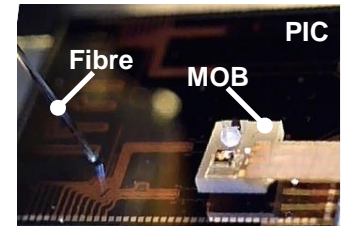
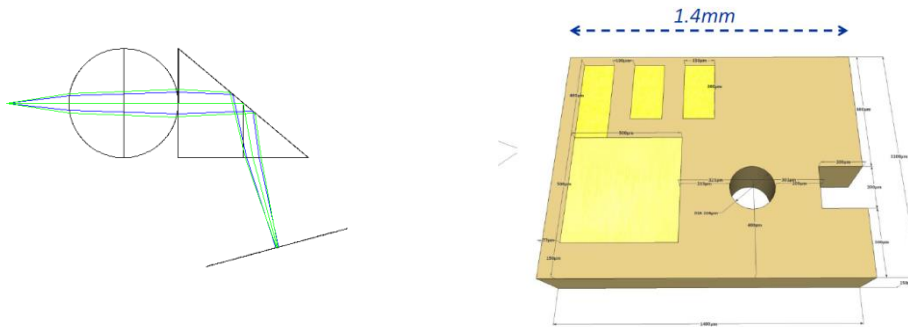


- Edge emitting lasers chip
 - Free space coupling
- => High level of customizability

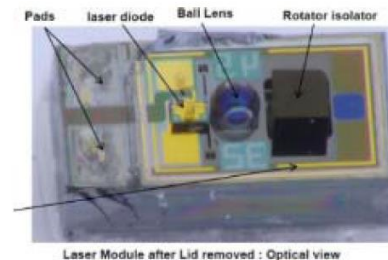
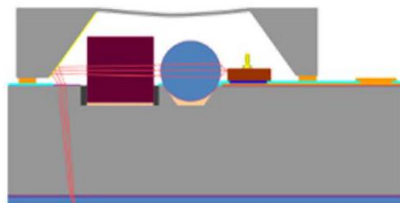
- Platform for biomedical applications:
Power / Wavelength (value and spectral range) / Linewidth / Polarization control

Introduction: MOB

- Optimal coupling with free-space optical components
- Low-Cost Fabrication and alignment
 - Passive assembly of the components
 - Active assembly of the MOB on the PIC



Luxtera (for high-speed interconnects)*



* P. De Dobbelaere et al, "Silicon-photonics-based optical transceivers for high-speed interconnect applications," in SPIE OPTO, 977503–977503, International Society for Optics and Photonics (2016).

Introduction: Project Requirements

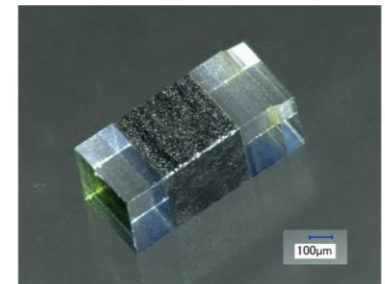
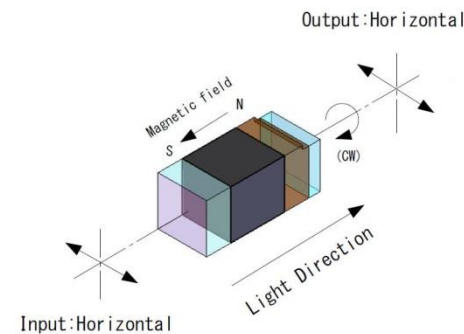


Early stage CARdio Vascular Disease Detection with Integrated Silicon Photonics

Demonstrate the concept of a mobile, low-cost device based on a silicon photonics integrated laser vibrometer .

Requirement for a 1550nm laser / Discrete mode / Linewidth 20MHz / Stabilization

- Discrete sub-mm isolator integration
 - >20dB isolation
 - Ensure high frequency stability
- Thermal management
 - AlN substrate ($300\text{W}\cdot\text{m}^{-1}\cdot\text{K}^{-1}$)
 - Close integration of thermistor
 - Avoid low-frequency drifts
- Optimal optical coupling
 - High Power required: >10mW in the waveguide



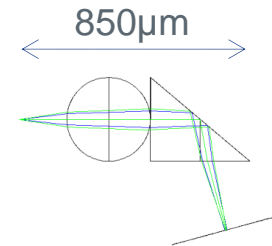
Outline

- Design:
 - Optical
 - Alignment tolerances study
 - Mechanical
- Assembly process
- Results:
 - Beam profile characterization
 - PIC alignment
 - Coupling

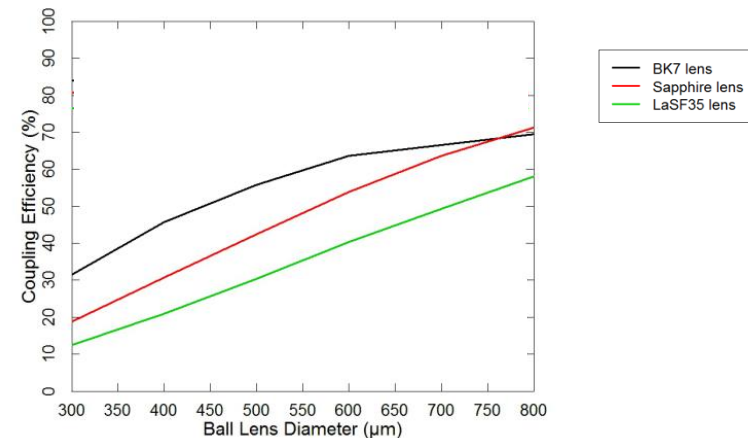
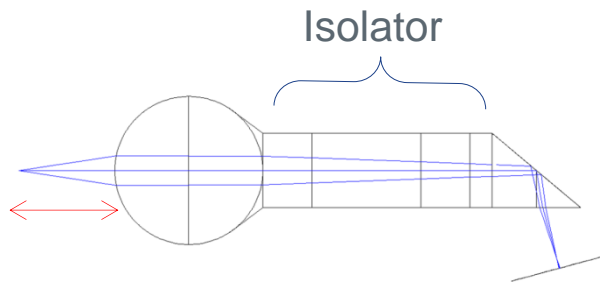
Optical Design

Challenges:

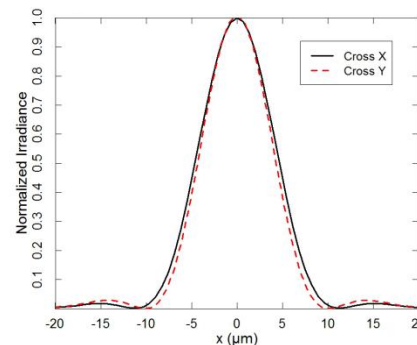
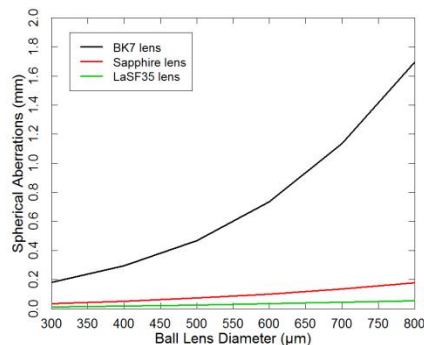
- Accommodate the additional 900 μm length and keep the NA conversion
- Manage passive assembly



- 1 ball lens:



→
Towards NA conversion

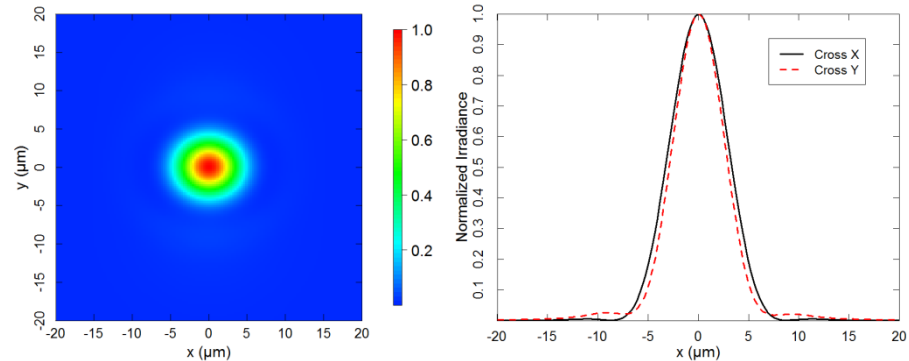
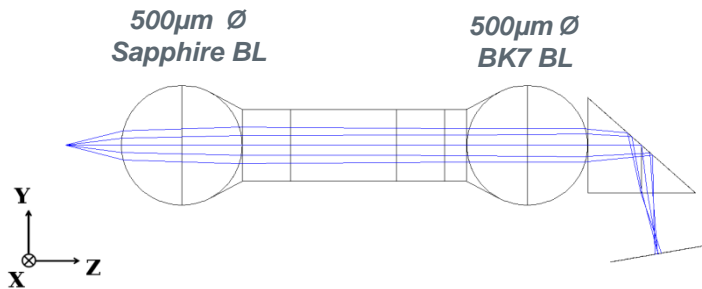


CE limited by:

- Ball lens size
- Spherical aberrations

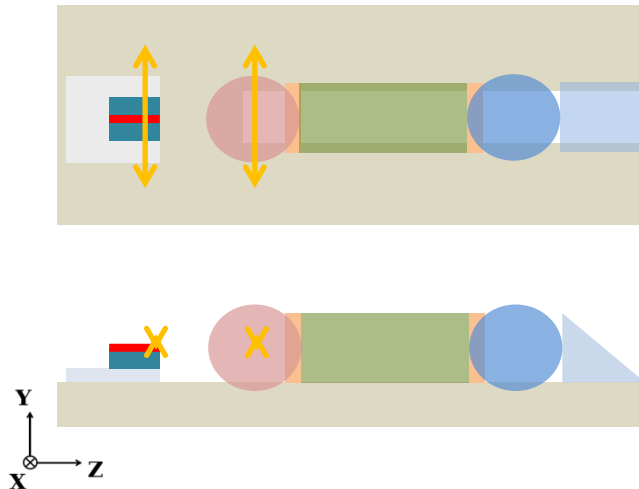
Optical Design

- 2 ball lenses:
 - Perfect NA conversion (i.e. beam spot size)
 $CE_{rec}=96\%$
 - Little aberrations
 - Collimated beam in the isolator



- Relatively tolerant to NA changes
 - NA 0.115/0.15 $\Rightarrow CE_{rec}=96\%$
 - NA 0.19/0.25 $\Rightarrow CE_{rec}=77\%$
- 2 lenses to align, more difficult?

Alignment Tolerances

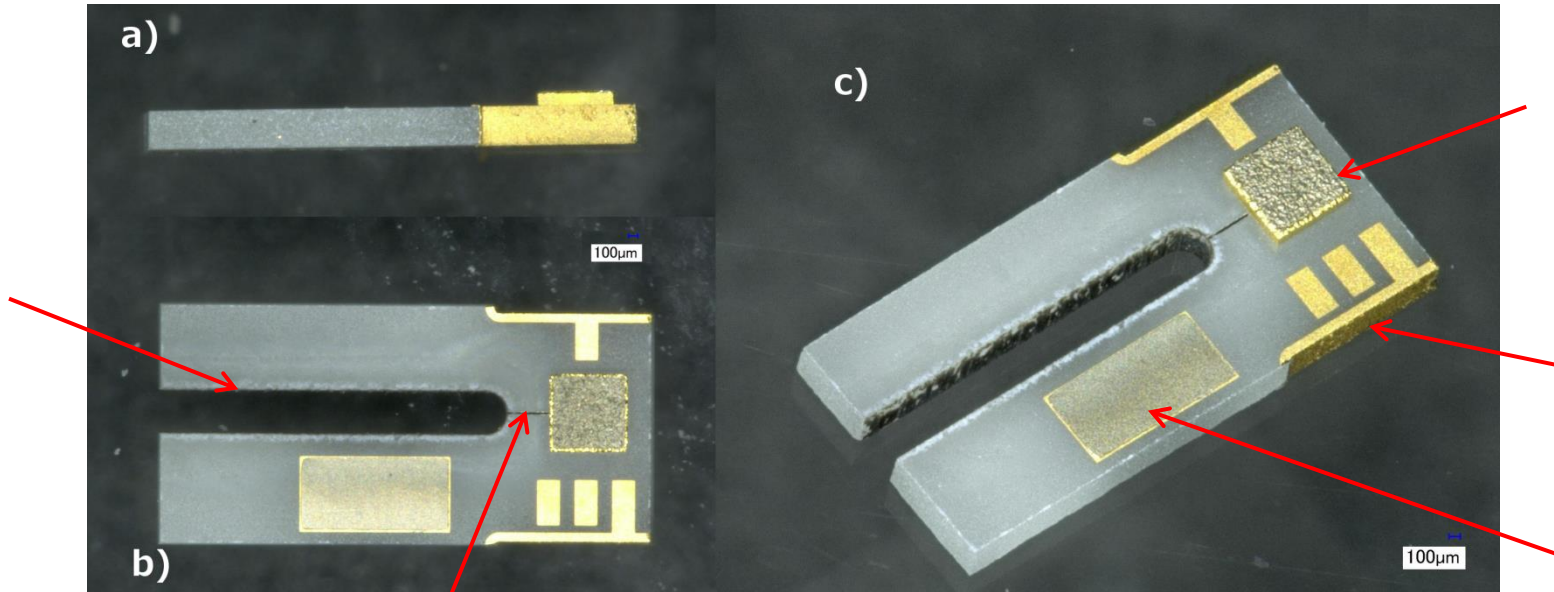


Misalignment	2 lenses MOB
Laser_DecenterX	$\pm 17\mu\text{m}$
Laser_TiltY	$\pm 5^\circ$
Laser_DecenterY	$\pm 15\mu\text{m}$
Laser_TiltX	$\pm 4^\circ$
BL1_DecenterX	$\pm 12\mu\text{m}$
BL1_DecenterY	$\pm 11\mu\text{m}$
BL2_DecenterX	$> \pm 30\mu\text{m}$
BL2_DecenterY	$> \pm 30\mu\text{m}$
FFL	$\pm 15\mu\text{m}$
BFL	0-60 μm

1dB losses misalignment tolerances

How are those alignment tolerances reached with a passive alignment process?

Bench Design

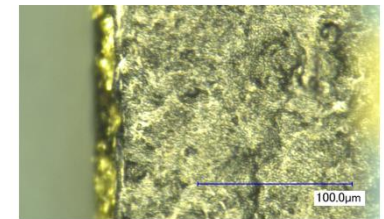
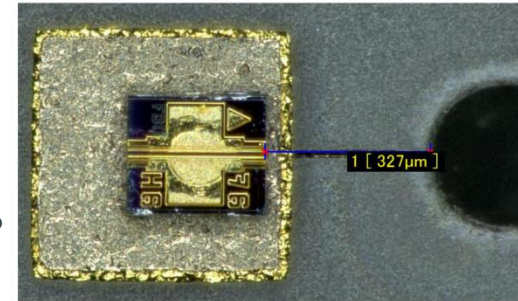


Features:

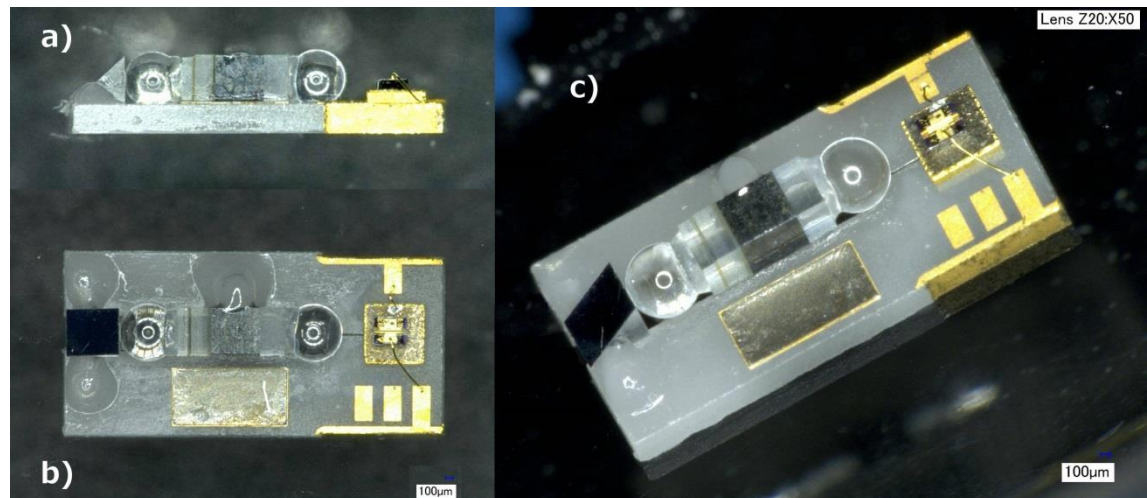
- Trench for passive alignment of the different components
 - 2 ball-lenses of the same diameter
- Alignment mark
 - For laser positioning
- Thick metallic pad for laser height accommodation
 - Optical Axis at 200µm from the surface
- Side contacts
- Pad for thermistor

Assembly

- Standard flip-chip of the laser die
 - Visual Alignment
 - AuSn reflow fixation
 - Position accuracy expected: $\pm 5\mu\text{m}$ / $\pm 1^\circ$
- Results:
 - Position accuracy obtained: $\pm 15\mu\text{m}$ / $\pm 5^\circ$
 - Roughness difficulty
 - Optimization in progress

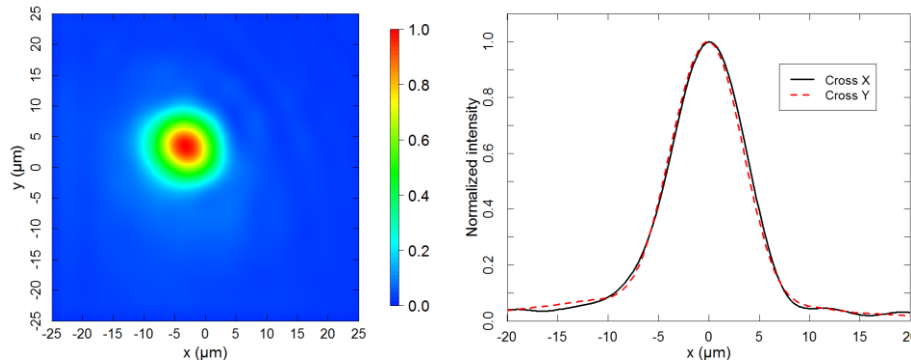


- Optical assembly:
 - Manual positioning
 - Gluing with UV-cure epoxy



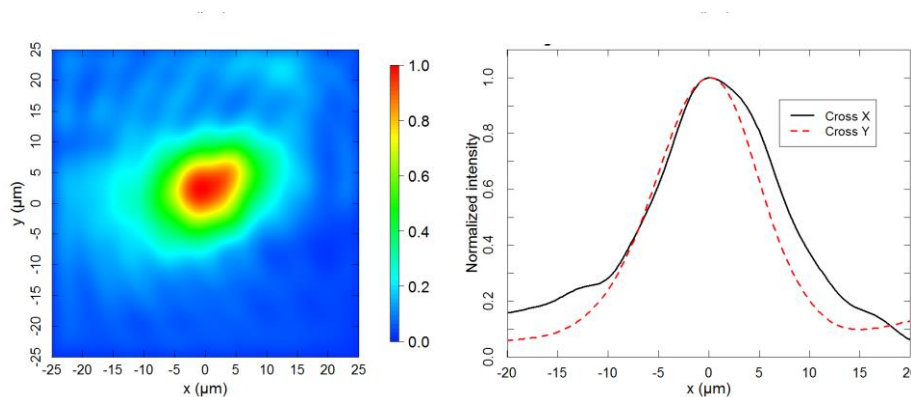
Beam profile characterization

- Beam intensity scanned at the focusing plan



“Good” alignment

- 14μm-15μm fitted gaussian profile diameter
- Symmetric
- Low aberrations
- Slightly defocus

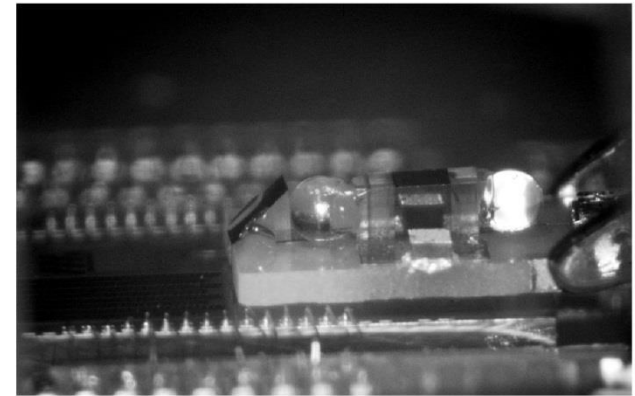
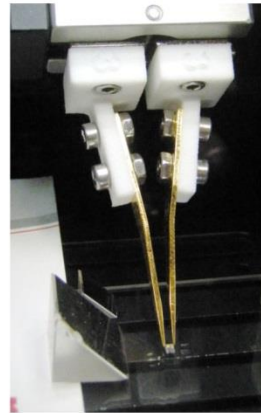


“Bad” alignment (*laser shifted 30μm laterally*)

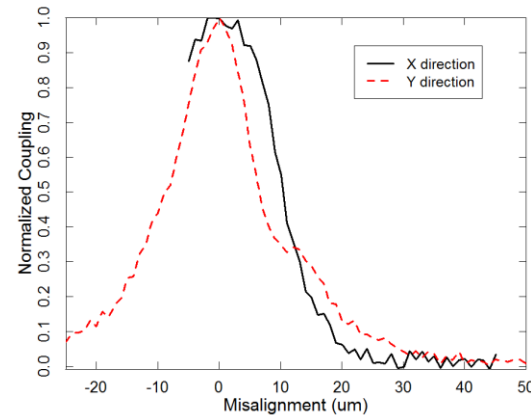
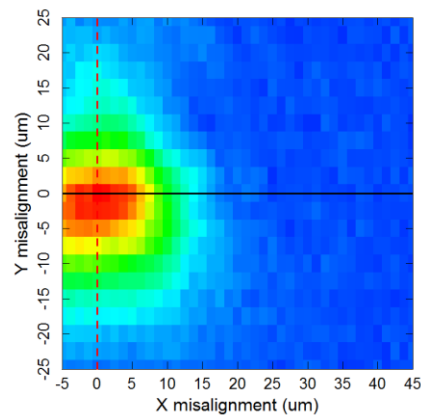
- 21μm-23μm fitted Gaussian profile diameter
- Astigmatism
- Diffraction patterns
- Strong defocus

PIC alignment

- Powering pick up tool:
 - 2 degrees of freedom optical alignment
 - Cost-effective process



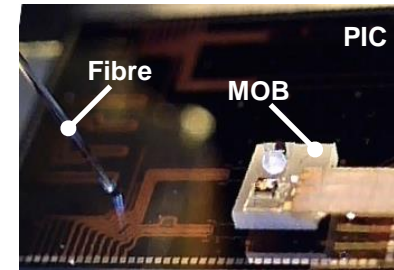
- Expected alignment tolerances:



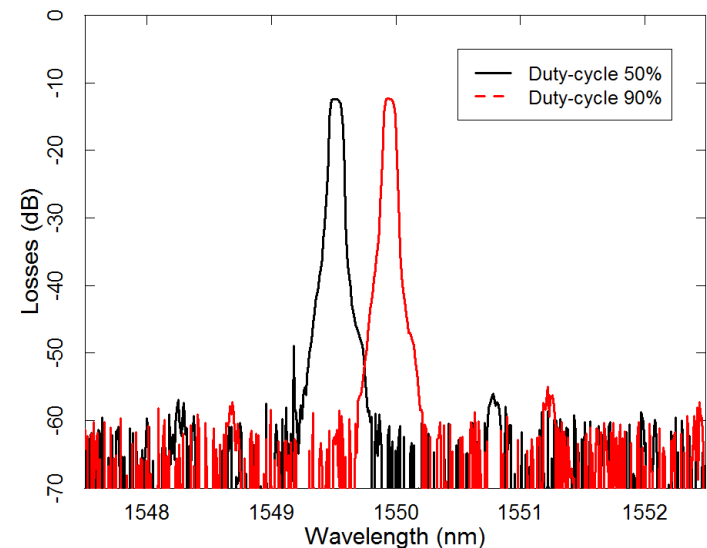
Coupling result: work in progress

- Integration penalty measurement:

$$Losses = \frac{MOB_{spectrum} / LaserPower}{Fiber_{spectrum} / SLD_{spectrum}}$$



- Discussion
 - Discrete Mode
 - Linewidth
 - Wavelength variation: 4°C shift
- Efficiency 12dB Losses
 - Standard package: coupling to fiber 4-5dB losses
 - Expected from perfect design 3dB
- Investigation:
 - Defocus 2-3dB
 - Isolator insertion losses
 - Additional surface reflection
 - DC measurement with thermal control required



Summary

- Platform for integration of fully processed laser chips
 - Thick pad and flip-chip process allows integration of most off-the-shelf edge emitting laser chips
- 2 ball-lenses optical design allows
 - maximized coupling efficiency
 - optimal integration of sub-millimetric isolator for high-frequency stabilization of the laser
- Low-cost assembly process
 - Passive assembly of the bench
 - 2 degrees of freedom active assembly

Next steps

- Optimize coupling efficiency
- Characterize laser stability
 - Optical isolation
 - Thermal management

Acknowledgments

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Tyndall National Institute,
Lee Maltings,
Dyke Parade,
Cork,
Ireland.
T12 R5CP

t: +353 21 490 4177
e: info@tyndall.ie
tyndall.ie

